

# Ken Collins

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/11854312/publications.pdf>

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15  
papers

357  
citations

933447

10  
h-index

996975

15  
g-index

15  
all docs

15  
docs citations

15  
times ranked

164  
citing authors

#	ARTICLE	IF	CITATIONS
1	Self-consistent simulation of very high frequency capacitively coupled plasmas. Plasma Sources Science and Technology, 2008, 17, 035003.	3.1	84
2	Effect of simultaneous source and bias pulsing in inductively coupled plasma etching. Journal of Applied Physics, 2009, 106, .	2.5	48
3	Extraction of negative ions from pulsed electronegative capacitively coupled plasmas. Journal of Applied Physics, 2012, 112, .	2.5	32
4	Effect of resonance in external radio-frequency circuit on very high frequency plasma discharge. Journal of Applied Physics, 2010, 107, .	2.5	31
5	Synchronous Pulse Plasma Operation upon Source and Bias Radio Frequencies for Inductively Coupled Plasma for Highly Reliable Gate Etching Technology. Japanese Journal of Applied Physics, 2009, 48, 08HD01.	1.5	28
6	Three-dimensional model of magnetized capacitively coupled plasmas. Journal of Applied Physics, 2009, 105, .	2.5	27
7	Influence of inhomogeneous magnetic field on the characteristics of very high frequency capacitively coupled plasmas. Journal of Applied Physics, 2010, 107, 053302.	2.5	23
8	Control of Plasma Uniformity Using Phase Difference in a VHF Plasma Process Chamber. IEEE Transactions on Plasma Science, 2008, 36, 1366-1367.	1.3	22
9	Recouping etch rates in pulsed inductively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2011, 29, .	2.1	22
10	Effect of azimuthally asymmetric reactor components on a parallel plate capacitively coupled plasma. Journal of Applied Physics, 2009, 106, .	2.5	10
11	On the scaling of rf and dc self-bias voltages with pressure in electronegative capacitively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, 021303.	2.1	9
12	Plasma-Profile Control Using External Circuit in a Capacitively Coupled Plasma Reactor. IEEE Transactions on Plasma Science, 2010, 38, 3241-3248.	1.3	7
13	Impact of Phase Shifted Coil Currents on Plasma Uniformity. IEEE Transactions on Plasma Science, 2011, 39, 2516-2517.	1.3	5
14	Self-organized pattern formation in radio frequency capacitively coupled discharges. Journal of Applied Physics, 2021, 129, .	2.5	5
15	Tailoring Ion Energy Distributions Using Pulsed Plasmas. IEEE Transactions on Plasma Science, 2011, 39, 2520-2521.	1.3	4